In the Claims:

Please amend claims 1 and 11 as follows:

(Currently Amended) A magnetoresistive film comprising:
an antiferromagnetic layer;

a first pinned ferromagnetic layer superposed on the antiferromagnetic layer, a base interfacial roughness being formed between the antiferromagnetic layer and the first pinned ferromagnetic layer;

an antiferromagnetic bonding layer superposed on the first pinned ferromagnetic layer;

a second pinned ferromagnetic layer superposed on the antiferromagnetic bonding layer;

a compound existing between the antiferromagnetic layer and the second pinned ferromagnetic layer;

a non-magnetic spacer layer superposed on the second pinned ferromagnetic layer, an interfacial roughness smaller than the base interfacial roughness being formed between the second pinned ferromagnetic layer and the non-magnetic spacer layer; and;

a free ferromagnetic layer superposed on the non-magnetic spacer layer;

a compound existing between the antiferromagnetic layer and the second pinned ferromagnetic layer.

2. (Original) The magnetoresistive film according to claim 1, wherein said antiferromagnetic layer is a polycrystalline layer of a regulated lattice structure.

.

- 3. (Original) The magnetoresistive film according to claim 2, wherein said compound comprises at least one of an oxide, a nitride, a sulfide and a carbide.
- 4. (Original) The magnetoresistive film according to claim 3, wherein said oxide, nitride, sulfide or carbide is a compound consisting of an element included in the antiferromagnetic bonding layer, and oxygen, nitrogen, sulfur or carbon.
- 5. (Original) The magnetoresistive film according to claim 4, wherein said antiferromagnetic bonding layer has a thickness in the range between 0.5nm and 0.9nm.
- 6. (Original) The magnetoresistive film according to claim 5, wherein said non-magnetic spacer layer has a thickness in the range between 1.9nm and 2.3nm.
 - 7-10. Withdrawn.

- 11. (Currently Amended) A layered polycrystalline structure film comprising:
- a first <u>crystalline</u> ferromagnetic <u>crystal</u> layer <u>having a base interfacial</u> roughness;

an antiferromagnetic bonding layer formed on the first <u>crystalline</u> ferromagnetic crystalling ferromagnetic bonding layer formed on the first <u>crystalline</u>

a second <u>crystalline</u> ferromagnetic <u>crystal</u> layer formed on the <u>epitaxial</u> antiferromagnetic bonding layer based on epitaxy; and

a compound existing between the antiferromagnetic bonding layer and the second <u>crystalline</u> ferromagnetic <u>erystal-layer</u>, <u>wherein</u>

said second crystalline ferromagnetic layer forms an interfacial roughness smaller than the base interfacial roughness.

- 12. (Original) The layered polycrystalline structure film according to claim 11, wherein said compound comprises at least one of an oxide, a nitride, a sulfide and a carbide.
- 13. (Original) The layered polycrystalline structure film according to claim 12, wherein said oxide, nitride, sulfide or carbide is a compound consisting of an element included in the antiferromagnetic bonding layer, and oxygen, nitrogen, sulfur or carbon.